



NEUTRAL DETERGENT

DP154

Low Surface Tension Neutral pH Detergent

VALTRON DP154 is a neutral pH detergent that is recommended for cleaning various ceramic substrates and components that are sensitive to acidic or alkaline detergent solutions. DP154 has low surface tension and strong ionic charge which is effective in removing small sub-micron particles, hydrocarbon films and light oils. VALTRON DP154 exhibits excellent solvent action, wettability, suspension and emulsification properties.

UNIQUE FEATURES

- Effective Penetration & Removal of Particles & Hydrocarbon Films
- Excellent Rinseability, Leaves No Residue
- 0.2 Micron Filtration
- Biodegradable Formulation
- Blend of Nonionic & Cationic Surfactants
- Low Surface Tension Formulation for Particle Removal



APPLICATION

VALTRON DP154 detergent is effective in contact and non-contact cleaning equipment for ultrasonic, megasonic, immersion and mechanical scrub applications. VALTRON DP154 is supplied in a liquid concentrate for dilution with deionized water. Typical dilution rates are 1.0 - 2.0% by volume, but may vary depending upon the type and quantity of contamination being removed.

PACKAGING

VALTRON DP154 detergent is available in 5 gallon (18.9 L) pails and 55 gallon (208 L) drums.

TYPICAL PHYSICAL PROPERTIES

Appearance	Clear, light amber liquid
Specific Gravity 60°F (15.6°C)	1.012
pH (concentrate)	7.0
Cloud Point (1.0% solution, v/v)	None - clear to 212°F (100°C)
Surface Tension (1.0% solution, v/v)	27.5 dynes/cm



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